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STN % Cas Japio, Inspec, USPAT

(FILE 'HOME' ENTERED AT 12:02:43 ON 11 SEP 2002)

FILE 'CA' ENTERED AT 12:02:46 ON 11 SEP 2002

L1 802 S OH(10A) (SILICA? OR SI2O3 OR SI(W)SUB(W)2(W)O(W)SUB(W)3) (10A) G
L2 7 S L1 AND (CMP OR POLISH? OR CHEMIPOLISH? OR CHEMIMECH? OR PLANAR
L3 7 S L1(P) (CMP OR POLISH? OR CHEMIPOLISH? OR CHEMIMECH? OR PLANAR

FILE 'JAPIO' ENTERED AT 12:05:14 ON 11 SEP 2002

L4 4 S L2

FILE 'INSP' ENTERED AT 12:06:23 ON 11 SEP 2002

L5 0 S L2

FILE 'CA' ENTERED AT 12:06:37 ON 11 SEP 2002

L6 7 S L3

FILE 'CA' ENTERED AT 12:07:08 ON 11 SEP 2002

L7 5227 S OH(10A) (SILICA? OR SI2O3 OR SI(W)SUB(W)2(W)O(W)SUB(W)3)
L8 80 S L7 AND (CMP OR POLISH? OR CHEMIPOLISH? OR CHEMIMECH? OR PLANAR
L9 69 S L8 NOT (L2 OR HYDROXYL?)
SET HIGH OFF
L10 69 S L9
SET HIGH ON
L11 69 S L10 AND OH

FILE 'JAPIO' ENTERED AT 12:12:02 ON 11 SEP 2002

L12 5 S L11

L13 5 S L9

FILE 'INSP' ENTERED AT 12:13:18 ON 11 SEP 2002

L14 1 S L11

FILE 'USPATFULL' ENTERED AT 12:14:05 ON 11 SEP 2002

L15 377 S L11
L16 4617 S SI(10W)OH
L17 80 S L16 AND L15
SET HIGH OFF
L18 80 S L17
SET HIGH ON
L19 80 S L16 AND L18
L20 297 S L15 NOT L19
L21 14 S L20 AND (CMP OR POLISH? OR CHEMIPOLISH? OR CHEMIMECH? OR PLANAR
SET HIGH OFF
L22 14 S L21 AND OH
SET HIGH ON
L23 14 S L22 AND OH
L24 283 S L20 NOT L23
SAVE POLISHL24/A L24
SET HIGH OFF
L25 47 S L24 AND (SEMICONDUCT? OR WAFER# OR CHIP#)
SET HIGH ON
L26 47 S L25 AND OH
L27 236 S L24 NOT L26
SAVE POLISHL27/A L27
DEL ETCHELL28/A
DEL ETCHELL29/A
DEL POLYSIL36/A
DEL RESISTL20/A
SAVE POLILSHL26/A L26
SET HIGH OFF

L28 236 S L27
 SET HIGH ON
L29 236 S L28 AND OH
 SAVE POLISHL29/A L29

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